

**PATENT APPLICATION**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q89627

Koichi TERASHIMA, et al.

Appln. No.: 10/544,783

Group Art Unit: 2812

Confirmation No.: 5339

Examiner: Pape A. SENE

Filed: August 8, 2005

For: METHOD FOR FORMING NICKEL SILICIDE FILM, METHOD FOR  
MANUFACTURING SEMICONDUCTOR DEVICE, AND METHOD FOR ETCHING  
NICKEL SILICIDE

**PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of December 23, 2008 to April 23, 2009.

The USPTO is directed and authorized to charge the statutory fee of \$130.00 and all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

Date: April 17, 2009